

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	55	wafer and (sheet adj resistivity) and boron and (thermal adj anneal)	USPAT	OR	OFF	2005/02/15 13:52
L2	46	wafer and (sheet adj resistivity) and boron and (thermal adj anneal) and implant	USPAT	OR	OFF	2005/02/15 13:53
L3	10	wafer and (sheet adj resistivity) and boron and (thermal adj anneal) and implant and (amorphous with silicon)	USPAT	OR	OFF	2005/02/15 13:53
L4	10	wafer and (sheet adj resistivity) and boron and (thermal adj anneal) and implant and (amorphous with silicon)and oxide	USPAT	OR	OFF	2005/02/15 14:52
L5	1224	(438/14).CCLS.	USPAT	OR	OFF	2005/02/15 13:56
L6	10	5 and (sheet adj resistivity)	USPAT	OR	OFF	2005/02/15 13:56
L7	666	(438/16).CCLS.	USPAT	OR	OFF	2005/02/15 14:52
L8	500	(356/72).CCLS.	USPAT	OR	OFF	2005/02/15 14:52
S1	1223	(438/14).CCLS.	USPAT	OR	OFF	2005/02/14 13:48
S2	8	S1 and monitor and silicon and particle and dopant and tool	USPAT	OR	ON	2005/02/14 13:50
S3	54	monitor and screen and oxide and wafer and dopant and boron and anneal and particle	USPAT	OR	ON	2005/02/14 13:51
S4	30	monitor and screen and oxide and wafer and dopant and boron and anneal and particle and silicon and amorphous	USPAT	OR	ON	2005/02/14 13:51
S5	7	monitor and screen and oxide and wafer and dopant and boron and anneal and particle and silicon and amorphous and sheet	USPAT	OR	ON	2005/02/14 13:52
S6	0	monitor and (screen adj oxide) and wafer and dopant and boron and anneal and particle and silicon and amorphous and sheet	USPAT	OR	ON	2005/02/14 13:52
S7	0	monitor and (screen with oxide) and wafer and dopant and boron and anneal and particle and silicon and amorphous and sheet	USPAT	OR	ON	2005/02/14 13:52